



JETSTAR series

RTCVD-RTA-RTO-RTN
Versatile RTP processor

Transfer your process
from development to
production
Wafer size up to 300mm

The Jipelec JetStar has been developed to meet the requirements of organizations performing large scale research and development or transferring a process to production.

This RTP tool has a manual loading system for your process development or pilot production. It can be upgraded to an automatic cassette-to-cassette system, allowing your process to move to production in the shortest time.

Multi-zone temperature control for enhanced uniformity, coupled with the temperature measurement and control system, provides accurate and repeatable thermal behavior from low to high temperature.



The extended temperature range, vacuum performance and gas mixing capability make it suitable for a large range of RTP and RTCVD processes.

Main features

Wafer sizes up to 300 mm
Pyrometer and thermocouple controllers
PID temperature control
Atmospheric and high vacuum process capability (10^{-7} mbar)
Evolutive and upgradable system from 200 to 300mm
Cold wall chamber technology
Up to 6 gas lines with MFCs
Process management software



Options

Cassette-to-cassette module
Turbomolecular pumping unit
Pressure controller
Heat exchanger for lamp cooling unit

Applications

RTA : Rapid Thermal Annealing, implant monitoring
RTO : Rapid Thermal Oxidation
RTN : Rapid Thermal Nitridation
RTD : Rapid Thermal Diffusion from spin-on dopants
Crystallization
Contact alloying
RTCVD processes
Densification
Firing

Features

Temperature range:	ambient to 1400°C
Ramp rate:	1°C/s to 200°C/s
Pyrometer control:	150°C to 1400°C
Dimensions (L/W/H):	1000x1050x2300 mm